X-ray Photoelectron Spectroscopy (XPS)

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Surface Analysis

The Study of the Outer-Most Layers of Materials (<100 \square).

Electron Spectroscopies

XPS: X-ray Photoelectron Spectroscopy

AES: Auger Electron Spectroscopy

EELS: Electron Energy Loss Spectroscopy

Ion Spectroscopies

SIMS: Secondary Ion Mass Spectrometry

SNMS: Sputtered Neutral Mass Spectrometry

ISS: Ion Scattering Spectroscopy

Introduction to X-ray Photoelectron Spectroscopy (XPS)

Introduction to X-ray Photoelectron Spectroscopy (XPS)

> What is XPS?- General Theory
> How can we identify elements and compounds?

- Instrumentation for XPS
- Examples of materials analysis with XPS

What is XPS?

X-ray Photoelectron Spectroscopy (XPS), also known as Electron Spectroscopy for Chemical Analysis (ESCA) is a widely used technique to investigate the chemical composition of surfaces.

What is XPS?

X-ray Photoelectron spectroscopy, based on the photoelectric effect,^{1,2} was developed in the mid-1960's by Kai Siegbahn and his research group at the University of Uppsala, Sweden.³

H. Hertz, Ann. Physik 31,983 (1887).
 A. Einstein, Ann. Physik 17,132 (1905). 1921 Nobel Prize in Physics.
 K. Siegbahn, Et. Al.,Nova Acta Regiae Soc.Sci., Ser. IV, Vol. 20 (1967).
 1981 Nobel Prize in Physics.

X-ray Photoelectron Spectroscopy Small Area Detection



X-ray excitation area ~1x1 cm². Electrons are emitted from this entire area

The Photoelectric Process



XPS spectral lines are identified by the shell from which the electron was ejected (1s, 2s, 2p, etc.).

The ejected photoelectron has kinetic energy:

KE=hv-BE-

Following this process, the atom will release energy by the emission of an Auger Electron.

Auger Relation of Core Hole



- L electron falls to fill core level vacancy (step 1).
- KLL Auger electron emitted to conserve energy released in step 1.
- The kinetic energy of the emitted Auger electron is: KE = E(K) - E(L2) - E(L3).

XPS Energy Scale

The XPS instrument measures the kinetic energy of all collected electrons. The electron signal includes contributions from both photoelectron and Auger electron lines.

XPS Energy Scale- Kinetic energy

 $KE = hv - BE - M_{spec}$

Where: BE= Electron Binding Energy KE= Electron Kinetic Energy Spec= Spectrometer Work Function

Photoelectron line energies: Dependent on photon energy. Auger electron line energies: Not Dependent on photon energy.

If XPS spectra were presented on a kinetic energy scale, one would need to know the X-ray source energy used to collect the data in order to compare the chemical states in the sample with data collected using another source.

XPS Energy Scale- Binding energy

 $BE = hv - KE - M_{spec}$

Where: BE= Electron Binding Energy KE= Electron Kinetic Energy Spec= Spectrometer Work Function

Photoelectron line energies: Not Dependent on photon energy. Auger electron line energies: Dependent on photon energy.

The binding energy scale was derived to make uniform comparisons of chemical states straight forward.

Fermi Level Referencing

Free electrons (those giving rise to conductivity) find an equal potential which is constant throughout the material.



2. At $kT << E_f$ (at room temperature kT=0.025 eV) f(E)=0.5 for $E=E_f$

Fermi Level Referencing



Sample/Spectrometer Energy Level Diagram- Conducting Sample



Because the Fermi levels of the sample and spectrometer are aligned, we only need to know the spectrometer work function, \mathbb{K}_{spec} , to calculate BE(1s).

Sample/Spectrometer Energy Level Diagram- Insulating Sample



A relative build-up of electrons at the spectrometer raises the Fermi level of the spectrometer relative to the sample. A potential E_{ch} will develop.

Binding Energy Referencing

 $BE = hv - KE - M_{spec} - E_{ch}$

Where: BE= Electron Binding Energy KE= Electron Kinetic Energy [X]_{spec}= Spectrometer Work Function E_{ch}= Surface Charge Energy

 E_{ch} can be determined by electrically calibrating the instrument to a spectral feature.

C1s at 285.0 eV Au4f_{7/2} at 84.0 eV

Where do Binding Energy Shifts Come From?

-or How Can We Identify Elements and Compounds?



Elemental Shifts

	Binding Energy (eV)		
Element	2p _{3/2}	3р	Δ
Fe	707	53	654
Со	778	60	718
Ni	853	67	786
Cu	933	75	858
Zn	1022	89	933

Electron-nucleus attraction helps us identify the elements

Elemental Shifts



Binding Energy Determination

The photoelectron's binding energy will be based on the element's final-state configuration.



The Sudden Approximation

Assumes the remaining orbitals (often called the passive orbitals) are the same in the final state as they were in the initial state (also called the *frozen-orbital approximation*). Under this assumption, the XPS experiment measures the negative Hartree-Fock orbital energy:

Koopman's Binding Energy

Е_{В,К} ₩ - ₩_{В,К}

Actual binding energy will represent the readjustment of the N-1 charges to minimize energy (relaxation):

 $E_{B} = E_{f}^{N-1} - E_{i}^{N}$

Binding Energy Shifts (Chemical Shifts)

Point Charge Model:

 $E_i = E_i^0 + kq_i + \bigvee_{i=1}^{\infty} q_i/r_{ij}$

E_B in atom i in given refernce state

Weighted charge of i

Potential at i due to surrounding charges





Chemical Shifts-Electronegativity Effects

Functional Group		Binding Energy (eV)
hydrocarbon	<u>C</u> -H, <u>C</u> -C	285.0
amine	<u>C</u> -N	286.0
alcohol, ether	<u>С</u> -О-Н, <u>С</u> -О-С	286.5
CI bound to C	<u>C</u> -Cl	286.5
F bound to C	<u>C</u> -F	287.8
carbonyl	<u>C</u> =O	288.0

Electronic Effects Spin-Orbit Coupling



Orbital=s l=0 s=+/-1/2 ls=1/2

Electronic Effects Spin-Orbit Coupling



Electronic Effects Spin-Orbit Coupling



Orbital=d l=2 s=+/-1/2 ls=3/2,5/2

Electronic Effects Spin-OrbitCoupling



Orbital=f l=3 s=+/-1/2 ls=5/2,7/2

Electronic Effects- Spin-Orbit Coupling







Final State Effects-Shake-up/ Shake-off

Results from energy made available in the relaxation of the final state configuration (due to a loss of the screening effect of the core level electron which underwent photoemission). $L(2p) \rightarrow Cu(3d)$

- Monopole transition: Only the principle quantum number changes. Spin and angular momentum cannot change.
- Shake-up: Relaxation energy used to excite electrons in valence levels to bound states (monopole excitation).
- Shake-off: Relaxation energy used to excite electrons in valence levels to unbound states (monopole ionization).



Figure 8. Examples of shake-up lines (s) of the copper 2p observed in copper compounds.

Final State Effects-Shake-up/ Shake-off

Ni Metal



Ni Oxide



Final State Effects- Multiplet Splitting

Following photoelectron emission, the remaining unpaired electron may couple with other unpaired electrons in the atom, resulting in an ion with several possible final state configurations with as many different energies. This produces a line which is split asymmetrically into several components.



Figure 10. Multiplet splitting of the Mn 3s.

Electron Scattering Effects Energy Loss Peaks

$$e_{ph} + e_{solid} \rightarrow e^{*}_{ph} + e^{**}_{solid}$$

Photoelectrons travelling through the solid can interact with other electrons in the material. These interactions can result in the photoelectron exciting an electronic transition, thus losing some of its energy (inelastic scattering).

Electron Scattering Effects Plasmon Loss Peak



Electron Scattering Effects Plasmon Loss Peak

Insulating Material



Quantitative Analysis by XPS

For a Homogeneous sample: I = NsDJLIAT

where: N = atoms/cm³ s = photoelectric cross-section, cm² D = detector efficiency J = X-ray flux, photon/cm²-sec L = orbital symmetry factor I = inelastic electron mean-free path, cm A = analysis area, cm² T = analyzer transmission efficiency Quantitative Analysis by XPS

N = I/sDJLIAT

Let denominator = elemental sensitivity factor, S

N = I / S

Can describe Relative Concentration of observed elements as a number fraction by:

 $C_x = N_x / SN_i$

 $C_x = I_x/S_x / S_i/S_i$

The values of S are based on empirical data.

Relative Sensitivities of the Elements



XPS of Copper-Nickel alloy



Comparison of Sensitivities



Instrumentation for X-ray Photoelectron Spectroscopy

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Instrumentation for XPS

Surface analysis by XPS requires irradiating a solid in an Ultra-high Vacuum (UHV) chamber with monoenergetic soft Xrays and analyzing the energies of the emitted electrons.

Why UHV for Surface Analysis?

Degree of Vacuum	Torr
Low Vacuum	10-
Medium Vacuum	10-4
High Vacuum	10.
Ultra-High Vacuum	10-11
	10 ⁻¹¹

Pressure

- Remove adsorbed gases from the sample.
- Eliminate adsorption of contaminants on the sample.
- Prevent arcing and high voltage breakdown.
- Increase the mean free path for electrons, ions and photons.

X-ray Photoelectron Spectrometer





X-ray Photoelectron Spectrometer



XPS at the 'Magic Angle'

Orbital Angular Symmetry Factor

 $L_A(g) = 1 + b_A (3sin^2g/2 - 1)/2$

where: g = source-detector angle b = constant for a given sub-shell and X-ray photon

At 54.7° the 'magic angle'

 $L_{A} = 1$

Electron Detection

Single Channel Detector



Electron distribution on analyzer detection plane



Electron Detection

Multi-channel Position Sensitive Detector (PSD)



Electron distribution on analyzer detection plane



X-ray Generation



Relative Probabilities of Relaxation of a K Shell Core Hole



Schematic of Dual Anode X-ray Source



Schematic of X-ray Monochromator



Applications of X-ray Photoelectron Spectroscopy (XPS)

XPS Analysis of Pigment from MummyArtwork





Analysis of Carbon Fiber- Polymer Composite Material by XPS





Woven carbon fiber composite V(E)/E

XPS analysis identifies the functional groups present on composite surface. Chemical nature of fiber-polymer interface will influence its properties.



Analysis of Materials for Solar Energy Collection by XPS Depth Profiling-

The amorphous-SiC/SnO₂ Interface



Data courtesy A. Nurrudin and J. Abelson, University of Illinois



Angle-resolved XPS Analysis of Self-Assembling Monolayers



Angle Resolved XPS Can Determine Over-layer Thickness Over-layer Coverage

Data courtesy L. Ge, R. Haasch and A. Gewirth, University of Illinois